

**b. Amendments to the Specification**

**At page 5, lines 8 – 19, please rewrite the paragraph as:**

The rough regions 34 are constructed to have a roughness suitable for producing the high resistivities that are desired for non-conductive portions 28 of organic semiconductor layer 22. Preferably, the rough regions 34 have thicknesses that are about 0.2 or more times the thickness of the nearby portions 28 of the organic semiconductor layer 22. Here, the thickness of a rough surface area is the vertical distance between highest peaks [[44]] and lowest valleys [[44]] on the surface area. Preferably, in the rough regions 34, the roughness density as measured by average lateral distances between adjacent peaks [[44,]] 45 is less than the vertical distance between the highest peaks and lowest valleys. For example, if organic semiconductor layer 22 is 50 nanometers (nm) thick, the adjacent rough region 34 should have a maximum peak-to-valley height of 10 nm or more and an average adjacent peak-to-peak separation of 10 nm or less.